WHAT IS CLAIMED IS:

An exposure apparatus comprising:

a projection optical system which projects a pattern of a first object to a second object by using an exposure beam in order to transfer the pattern from the first object onto the second object;

a diaphragm which sets a numerical aperture of said projection optical system; and

a mechanism which keeps temperature of said diaphragm substantially constant during an exposure operation by said projection optical system.

- 2. An apparatus according to Claim 1, wherein said mechanism comprises a fluid circulation system, which is provided with said diaphragm, in which a temperature controlled fluid circulates.
- 3. An apparatus according to Claim 2, wherein said mechanism controls the temperature of said diaphragm to be almost the same as that of said projection optical system, during the exposure operation.
- 4. An appearatus according to Claim 3, further comprising a constant temperature system for said projection

optical system, said constant temperature system providing the temperature controlled first to said mechanism.

- 5. An apparatus according to Claim 1, wherein said mechanism comprises a Peltier element.
- 6. An apparatus according to Claim 1, further comprising a sensor which detects temperature information of said diaphragm, wherein the temperature of said mechanism is controlled based on the sensor output.
 - 7. An apparatus according to Claim 6, wherein said sensor is located at a position not being irradiated with the exposure beam.
 - 8. An apparatus according to Claim 7, wherein said sensor is provided on said diaphragm, on a side facing the second object.
 - 9. An apparatus according to Claim 1, wherein said diaphragm comprises an iris diaphragm.
 - 10. An apparatus according to Claim 1, wherein said diaphragm comprises a turret having a plurality of openings.

11. An apparatus according to Claim 1, further comprising a reticle stage for holding a reticle as the first object, a wafer stage for holding a wafer as the second object, and said projection optical system comprises an illumination optical system.

12. A micro-device manufacturing method comprising:

projecting, through a projection optical system, a

pattern of a reticle to a wafer by using an exposure beam,

in order to transfer the pattern from the reticle onto the

water;

setting a numerical aperture of the projection optical system by a diaphragm;

keeping temperature of the diaphragm substantially constant during an exposure operation by the projection optical system; and

manufacturing a micro-device from the wafer.

- 13. A method according to Claim 12, wherein said keeping step comprises keeping the temperature of the diaphragm by circulating a fluid proximate to the diaphragm.
- 14. A method according to Claim 13, wherein the temperature of the diaphragm is kept to be almost the same as that of the projection optical system, during the

exposure operation.

- 15. A method according to Claim 14, further comprising controlling temperature of the projection optical system as well as that of the diaphragm.
- 16. A method according to Claim 12, wherein said keeping step comprises keeping the temperature of the diaphragm using a Reltier element.
- 17. A method according to Claim 12, further comprising detecting temperature information of the diaphragm with a sensor, and controlling the temperature of the diaphragm based an output of the sensor.
- 18. A method according to Claim 17, further comprising providing the sensor at a location not being irradiated with the exposure beam.
- 19. A method according to Claim 18, further comprising providing the sensor on the diaphragm on a side facing the second object.
- 20. A method according to Claim 12, wherein the diaphragm comprises an iris diaphragm.

- 21. A method according to Claim 12, wherein the diaphragm comprises a turret having a plurality of openings.
- 22. A method according to Claim 12, wherein said manufacturing step comprises a resist process and a development process.

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